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List of Reference Symbols

- 100 Integrated circuit
- 101 Silicon substrate
- 102 Contact-making element
- 103 First field-effect transistor
- 104 Second field-effect transistor
- 105 Gate region
- 106 Gate region
- 200 First layout view of an integrated circuit
- 201 First field-effect transistor
- 202 Second field-effect transistor
- 203 Common gate line
- 203a First gate component
- 203b Second component
- 203c First course direction
- 203d Second course direction
- 203e Third course direction
- 203f Fourth course direction
- 204 Active region
- 204a First course direction
- 204b Second course direction
- 205 Active region
- 205a First course direction
- 205b Second course direction
- 206 First square contact-making element
- 207 Second square contact-making element
- 208 Third square contact-making element
- 300 Second layout view of an integrated circuit
- 301 First rectangular contact-making element
- 301a Third course direction
- 301b Fourth course direction
- 302 Second rectangular contact-making element
- 302a Third course direction
- 302b Fourth course direction
- 303 Third rectangular contact-making element
- 303a Third course direction
- 303b Fourth course direction
- 401 Lithography device

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405 Silicon wafer
406a Processed chips
406b Unprocessed chips
406c Chip to be processed
407 Aligning optical arrangement
408 Reticle
409 Lens
410 Prealigning optical arrangement
411 Laser interferometer
412 Mirror area
413 xy table
414 Objective
415 Carrier element
440 Flow diagram
450 First method step
455 Second method step
460 Third method step
465 Fourth method step
470 Fifth method step
475 Sixth method step